NOV 13 2006

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re application of: Wu et al.

Attorney Docket No.: NOVLP097/NVLS-

2906

Application No.: 10/807,680

Examiner: Not yet assigned

Filed: March 23, 2004

Group: 2812

Title: METHODS OF POROGEN REMOVAL

FOR POROUS LOW DIELECTRIC CONSTANT FILMS USING PLASMA

TREATMENTS

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on November 7,2006 in an envelope addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22318-1450.

Signed

Tara Hayden

INFORMATION DISCLOSURE STATEMENT 37 CFR §§1.56 AND 1.97(b)

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NOVLP097).

Respectfully submitted,

BEYER WEAVER & THOMAS, L&P

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Form 1449 (Modified)

Information Disclosure Statement By Applicant

(Use Several Sheets if Necessary)

Atty Docket No.

NOVLP097/ NVLS-2906

Applicant: Wu et al.

Filing Date March 23, 2004 Application No.:

10/807,680

Group 2812

U.S. Patent Documents

			CIOT I MITTIE				
Examiner						Sub-	Filing
Initial	No.	Patent No.	Date	Patentee	Class	class	Date
	A1	7,094,713 B1	08.22.06	Niu et al.			
	A2	6,306,564	10.2001	Mullee, William H.			
	A3	2003/0066544 A1	04.2003	Jur et al.			
	A4	6,149,828 A	11.2000	Vaartstra, Brian A.			
	A5	6,943,121 B2	09.2005	Leu et al.			
	A6	2004/0102032 A1	05.2004	Kloster et al.			
	A7	2006/0110931 A1	05.2006	Fukazawa et al.			
	A8	7,087,271 B2	08.2006	Rhee et al.			
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Other Documents

		Other Documents			
Examiner					
Initial	No.				
	C1	U.S. Office Action mailed September 8, 2006, from U.S Application No. 10/404,69			
		[Atty Dkt No. NOVLP064/NVLS-794].			
	C2	U.S. Office Action mailed September 7, 2006, from U.S Application No. 10/820,52			
		[Atty Dkt No. NOVLP091/NVLS-2889].			
	C3	C3 U.S. Office Action mailed July 12, 2006, from U.S Application No. 10/672,305 [Att			
		Dkt No. NOVLP069/NVLS-2821].			
	C4 Wu et al., "Methods for Fabricating High Hardness/Modules Low Dielectric Constant				
		Materials," Novellus Systems, Inc., Appln No. 11/369,658, filed March 6, 2006, pp. 1-33. [NOVLP148/NVLS-3111]			
	C5	Dhas et al., "Method of Reducing Defects in PECVD TEOS Films," Novellus			
		Systems, Inc., Appln No. 11/396,303, filed March 30, 2006, pp. 1-21.			
	<u> </u>	[NOVLP160/NVLS-3168]			
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Examiner		Date Considered			

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.